

Docket No.: M4065.0319/P319
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Ronald A. Weimer, et al.

Application No.: 09/296,835

Group Art Unit: 2813

Filed: April 22, 1999

Examiner: E. Kielin

For: FABRICATION OF DRAM AND OTHER
SEMICONDUCTOR DEVICES WITH AN
INSULATING FILM USING A WET
RAPID THERMAL OXIDATION PROCESS

AMENDMENT

Box Non-Fee Amendment
Commissioner for Patents
Washington, DC 20231

Dear Sir:

This is in response to the Office Action dated November 21, 2000 (Paper No. 11). Concurrently herewith, Applicants have petitioned for a one-month extension of time and have paid the appropriate fee. Consequently, this response is timely filed by March 21, 2001. Please amend the above-identified U.S. Patent application as follows

IN THE CLAIMS:

✓
Please cancel claim 7.

Please rewrite claim 1 as in the Replacement Claims.

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T. Flowers

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